

Global Cr-Si Alloy Sputtering Target Market Growth 2026-2032

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Abstracts

The global Cr-Si Alloy Sputtering Target market size is predicted to grow from US\$ 5.91 million in 2025 to US\$ 9.59 million in 2032; it is expected to grow at a CAGR of 7.2% from 2026 to 2032.

In 2025, the global production of Cr-Si alloy sputtering targets was 13,757 pieces, with an average price of US\$439 per piece.

A Cr–Si alloy sputtering target is a high-purity, composition-tunable chromium–silicon target used in PVD (typically magnetron sputtering) to deposit Cr–Si/SiCr thin films whose electrical and functional properties are engineered by adjusting the Cr/Si ratio (unlike stoichiometric chromium silicides such as CrSi₂ or Cr₃Si with fixed phase chemistry). Its key characteristics include broad resistivity tunability, the ability to achieve low/near-zero TCR under optimized composition and process windows, good thermal/chemical stability, and strong sensitivity to microstructural uniformity, density/porosity, particle control, and bonding quality, which collectively determine film defectivity and long-campaign stability. The most common application scenarios are resistive films for thin-film resistors and resistor networks (including high-reliability and automotive-grade sensing/measurement structures), MEMS/sensor functional layers where stable sheet resistance is required, and selected interface/barrier or optical/functional layers where Cr–Si chemistry and stability are advantageous. Current development is broadly moving toward higher purity and tighter impurity control (especially O/N/C), improved densification and microstructure control (often via advanced PM/HIP routes), cleaner machining/packaging to reduce particles, and stronger data-driven qualification (life-stage stability of Rs/TCR over target erosion), reflecting the same industry trajectory seen across high-end sputtering materials: fewer “commodity targets,” more process-validated target systems delivered with application

engineering and change control for semiconductor and precision passive markets.

Expanding PVD consumption and “materials intensity” in semiconductor manufacturing. Cr-Si alloy targets ride the same structural tailwinds as the broader sputtering-target ecosystem: recovering wafer starts, continued fab investments, and rising materials intensity per wafer drive target consumption and pricing power. Industry market trackers project sputtering-target revenues growing strongly in the near term and trending toward a larger market size by 2030, supported by improving semiconductor demand and policy-driven capacity buildout. This matters for Cr-Si because customers increasingly prefer “process-validated target systems” (target + backing + bonding + cleanliness + change control), lifting the value content per shipped target even when unit volumes are stable.

Downstream pull from precision thin-film resistors and high-reliability electronics (automotive, industrial, instrumentation). Cr-Si/SiCr resistive films are a proven resistor-film family with an established IP base (DC/RF sputtering from a Si/Cr target, followed by thermal processing to tune sheet resistance and TCR). On the component side, long-term drift/stability is a purchase driver: published industry materials show the “potential” of CrSi thin-film systems for precision applications, and process/alloy optimization has been used to improve drift performance at elevated temperatures—precisely the reliability window demanded by automotive-grade electronics. As automotive electronics and industrial control continue to push tighter tolerance and higher temperature capability, the addressable demand for stable thin-film resistor materials—and therefore their upstream targets—rises.

R&D investment aimed at tuning electrical properties (TCR/resistivity) and robustness. The market is also pulled by continuous R&D to widen the manufacturable property window (resistivity, TCR sign control, drift) using composition/process engineering—e.g., co-sputtering and annealing studies show TCR can be shifted from negative to positive with thermal treatment and alloying. This R&D push expands use cases for Cr-Si films beyond “legacy thin-film resistors” into more specialized sensor/MEMS and precision analog functions where predictable sheet resistance and low drift are essential.

LP Information, Inc. (LPI) ' newest research report, the “Cr-Si Alloy Sputtering Target Industry Forecast” looks at past sales and reviews total world Cr-Si Alloy Sputtering Target sales in 2025, providing a comprehensive analysis by region and market sector of projected Cr-Si Alloy Sputtering Target sales for 2026 through 2032. With Cr-Si Alloy Sputtering Target sales broken down by region, market sector and sub-sector, this

report provides a detailed analysis in US\$ millions of the world Cr-Si Alloy Sputtering Target industry.

This Insight Report provides a comprehensive analysis of the global Cr-Si Alloy Sputtering Target landscape and highlights key trends related to product segmentation, company formation, revenue, and market share, latest development, and M&A activity. This report also analyzes the strategies of leading global companies with a focus on Cr-Si Alloy Sputtering Target portfolios and capabilities, market entry strategies, market positions, and geographic footprints, to better understand these firms' unique position in an accelerating global Cr-Si Alloy Sputtering Target market.

This Insight Report evaluates the key market trends, drivers, and affecting factors shaping the global outlook for Cr-Si Alloy Sputtering Target and breaks down the forecast by Type, by Application, geography, and market size to highlight emerging pockets of opportunity. With a transparent methodology based on hundreds of bottom-up qualitative and quantitative market inputs, this study forecast offers a highly nuanced view of the current state and future trajectory in the global Cr-Si Alloy Sputtering Target.

This report presents a comprehensive overview, market shares, and growth opportunities of Cr-Si Alloy Sputtering Target market by product type, application, key manufacturers and key regions and countries.

Segmentation by Type:

Cr-Si (Cr₆₀, Si

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